L Number	Hits	Search Text	DB	Time stamp
1	10	koshiro near ochiai.in.	USPAT;	2004/02/10 13:07
-			US-PGPUB;	
	į		EPO; JPO;	
		· 1	DERWENT	
2	7360	(methacrylate or acrylate) and wash\$3 and oxalic	USPAT;	2004/02/10 13:09
-			US-PGPUB;	
			EPO; JPO;	
	İ		DERWENT	
3	553	(methacrylate or acrylate) and wash\$3 same oxalic	USPAT;	2004/02/10 13:09
,	333	(monatory last of well-state)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
4	532	(methacrylate or acrylate) and wash\$3 same oxalic near acid	USPAT;	2004/02/10 13:10
*	332	(monacrylate of derylate) and reserve states	US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	
_	95186	metal near3 remov\$3	USPAT;	2004/02/10 13:11
5	93160	nictal lical 3 telliov \$5	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	4.0	(metal near3 remov\$3) and ((methacrylate or acrylate) and wash\$3 same	USPAT;	2004/02/10 13:11
6	40		US-PGPUB;	
		oxalic near acid)	EPO; JPO;	
			DERWENT	
	106664	the control of the co	USPAT;	2002/12/03 14:14
-	496664	poly(meth)acrylate and metal near content	US-PGPUB;	
	-		EPO; JPO;	
			DERWENT	
		1 () 1 ()	USPAT;	2002/12/02 14:05
-	496901	poly(meth)acrylate and metal near content	US-PGPUB;	2002/12/02 11:05
			EPO; JPO;	
			DERWENT	
		1 least room outroation	USPAT;	2002/12/02 14:00
-	4530	(poly(meth)acrylate and metal near content) and solvent near extraction	US-PGPUB;	2002/12/02 11.00
			EPO; JPO;	
			DERWENT	
			USPAT;	2002/12/02 14:02
_	412	((poly(meth)acrylate and metal near content) and solvent near extraction)	1	2002/12/02 14.02
		and acid near3 wash\$3	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 14:03
-	0	(((poly(meth)acrylate and metal near content) and solvent near extraction)	USPAT;	2002/12/02 14:03
		and acid near3 wash\$3) and polyprotic near acid	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 14:02
_	28	(((poly(meth)acrylate and metal near content) and solvent near extraction)	USPAT;	2002/12/02 14:03
		and acid near3 wash\$3) and polycarboxylic near acid	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	496458	poly(meth)acrylate same metal near content	USPAT;	2002/12/02 14:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	496443	poly(meth)acrylate same reduced near metal near content	USPAT;	2002/12/02 14:13
	1,501.43	F/\///////	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	496459	poly(meth)acrylate same reduced same metal same content	USPAT;	2002/12/02 14:08
-	470439	port (mont) and the country to the c	US-PGPUB;	1
			EPO; JPO;	
			DERWENT	
	504390	poly(meth)acrylate same metal	USPAT;	2002/12/02 14:09
-	304390	poly(mem)acrylate same metar	US-PGPUB;	
			1	1
			EPO; JPO;	

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7	853	(poly(meth)acrylate same reduced same metal same content) same solvent	USPAT; US-PGPUB;	2002/12/02 14:14
		same extraction	EPO; JPO; DERWENT	
-	63722	solvent same extraction	USPAT;	2002/12/02 14:14
			US-PGPUB; EPO; JPO;	
			DERWENT	2002/12/02 14 10
-	4	((poly(meth)acrylate same reduced same metal same content) same solvent same extraction) same aqueous near acid	USPAT; US-PGPUB;	2002/12/02 14:19
		Solvent Same extraction, same aqueous near acre	EPO; JPO;	
	496858	poly(meth)acrylate same photoresist	DERWENT USPAT;	2002/12/02 16:17
-	470030	poly(meth/acryrate same photoresist	US-PGPUB;	
		·	EPO; JPO; DERWENT	
-	3	polyacrylate same photoresist and metal near content	USPAT;	2002/12/02 14:21
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	159	polyacrylate same photoresist	USPAT;	2002/12/02 16:06
			US-PGPUB; EPO; JPO;	
			DERWENT	2002/12/02 17 17
-	887236	poly(meth)acrylate same photoresistsame purif\$8	USPAT; US-PGPUB;	2002/12/02 16:17
			EPO; JPO;	
	496445	poly(meth)acrylate same photoresist same purif\$8	DERWENT USPAT;	2002/12/02 16:26
-	470443	pory(meth)acrytate same photoresist same purities	US-PGPUB;	2002/12/02 10:20
			EPO; JPO; DERWENT	
_	497666	poly(meth)acrylate same purif\$8	USPAT;	2002/12/02 16:18
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	1367	(poly(meth)acrylate same photoresist same purif\$8) same metal same	USPAT; US-PGPUB;	2002/12/02 16:19
		content	EPO; JPO;	
		2000	DERWENT	2002/12/02 16:20
-	40	((poly(meth)acrylate same photoresist same purif\$8) same metal same content) and wash\$3 near3 acid	USPAT; US-PGPUB;	2002/12/02 16:20
			EPO; JPO;	
_	245857	purif\$8 same process same poly(meth)acrylate	DERWENT USPAT;	2002/12/02 16:28
			US-PGPUB;	
			EPO; JPO; DERWENT	
-	17	(purif\$8 same process same poly(meth)acrylate) and reduced near metal	USPAT;	2002/12/02 16:31
		near content	US-PGPUB; EPO; JPO;	
			DERWENT	
-	8	ochiai near koshiro.in.	USPAT; US-PGPUB;	2002/12/02 16:49
		·	EPO; JPO;	
	3	"6258507"	DERWENT USPAT;	2002/12/02 16:50
		323337	US-PGPUB;	
			EPO; JPO; DERWENT	
_	252194	purif\$8 same poly(meth)acrylate	USPAT;	2002/12/02 16:51
		·	US-PGPUB; EPO; JPO;	
			DERWENT	

1				
[-,	1256	(purif\$8 same poly(meth)acrylate) same photoresist	USPAT;	2002/12/02 17:06
			US-PGPUB;	
			EPO; JPO; DERWENT	
		(/ taba at (ant) and the area at the second motel some		2002/12/02 16:53
-	4	((purif\$8 same poly(meth)acrylate) same photoresist) same metal same	USPAT; US-PGPUB;	2002/12/02 10:33
		content	EPO; JPO;	
			DERWENT	
	26	((purif\$8 same poly(meth)acrylate) same photoresist) and metal same	USPAT;	2002/12/02 16:53
-	36	content	US-PGPUB;	2002/12/02 10/02
		Content	EPO; JPO;	
			DERWENT	
	8	((purif\$8 same poly(meth)acrylate) same photoresist) same metal near	USPAT;	2002/12/02 17:09
		ions	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	820	metal near ions near removal	USPAT;	2002/12/03 17:13
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/22 17 17
-	80	(purif\$8 same poly(meth)acrylate) and (metal near ions near removal)	USPAT;	2002/12/02 17:16
]		US-PGPUB;	
			EPO; JPO; DERWENT	
		No	USPAT;	2002/12/02 17:26
-	12	(metal near ions near removal) same aqueous near acid	US-PGPUB;	2002/12/02 17.20
			EPO; JPO;	
			DERWENT	
	1	(metal near ions near removal) and wash\$3 near aqueous near acid	USPAT;	2002/12/02 17:27
-	1	(metal hear folis hear removar) and waships hear aqueous hear acid	US-PGPUB;	
*			EPO; JPO;	
			DERWENT	
_	235455	purif\$7 near poly(meth)acrylate	USPAT;	2002/12/03 09:52
			US-PGPUB;	
			EPO; JPO;	ļ
			DERWENT	
-	24269	wash near aqueous near acid or solvent near extraction	USPAT;	2002/12/03 09:54
			US-PGPUB;	
			EPO; JPO;	
		at was a success man said	DERWENT USPAT;	2002/12/03 09:54
-	41	wash near aqueous near acid	USPAT; US-PGPUB;	2002/12/03 07.34
			EPO; JPO;	
	,		DERWENT	
_	2131	(purif\$7 near poly(meth)acrylate) and (wash near aqueous near acid or	USPAT;	2002/12/03 09:54
		solvent near extraction)	US-PGPUB;	
		<i>'</i>	EPO; JPO;	
			DERWENT	
-	276	aqueous near acid near extraction	USPAT;	2002/12/03 09:54
		+	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 00:55
-	9485	aqueous near acid and extraction	USPAT;	2002/12/03 09:55
			US-PGPUB;	
			EPO; JPO; DERWENT	
	36	(purif\$7 near poly(meth)acrylate) and (aqueous near acid near extraction)	USPAT;	2002/12/03 09:56
-	36	(purity) near pory(metri)acryrate) and (aqueous near acid near extraction)	US-PGPUB;	2502,12,05 07.50
			EPO; JPO;	
			DERWENT	
-	0	polyacrylate and purif7	USPAT;	2002/12/03 09:56
		1 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2 2	US-PGPUB;	
			EPO; JPO;	
	1		DERWENT	

	4409	polyacrylate and purif\$7	USPAT;	2002/12/03 10:08
			US-PGPUB; EPO; JPO;	
			DERWENT	
	7450	polyacrylate and purif\$7	USPAT;	2002/12/03 09:57
-	7430	poryacryrate and purity	US-PGPUB;	
			EPO; JPO;	
,			DERWENT	
	248	(polyacrylate and purif\$7) and photoresist	USPAT;	2002/12/03 09:57
		(posyum) and p = ; ==== p==== :-	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	4	polyacrylate and trace near metal near ion near remov\$3	USPAT;	2002/12/03 10:09
			US-PGPUB;	
			EPO; JPO;	
	40	(1 1 1 (1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	DERWENT USPAT;	2002/12/03 10:11
-	40	(polyacrylate and metal near ion near remov\$3) and wash	US-PGPUB;	2002/12/03 10.11
			EPO; JPO;	
			DERWENT	
	120	polyacrylate and metal near ion near remov\$3	USPAT;	2002/12/03 10:11
	120	polytecijiaio and moun nom nom nom nom nom nom nom nom nom no	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	169038	polymerization and poly(meth)acrylate and extraction	USPAT;	2002/12/03 16:08
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 14:16
	100	(polymerization and poly(meth)acrylate and extraction) and aqueous near	USPAT; US-PGPUB;	2002/12/03 14:16
		oxalic near acid	EPO; JPO;	
			DERWENT	
_	845	(polymerization and poly(meth)acrylate and extraction) and metal near	USPAT;	2002/12/03 15:04
	0.5	remov\$3	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	102	((polymerization and poly(meth)acrylate and extraction) and metal near	USPAT;	2002/12/03 14:23
		remov\$3) and photoresist	US-PGPUB;	
			EPO; JPO; DERWENT	
	_	((polymerization and poly(meth)acrylate and extraction) and metal near	USPAT;	2002/12/03 15:04
-	0	remov\$3) and aqueous near oxalic	US-PGPUB;	2002/12/03 13:01
		Cinovasy and aqueous near oxune	EPO; JPO;	-,
			DERWENT	
-	101	(polymerization and poly(meth)acrylate and extraction) and aqueous near	USPAT;	2002/12/03 15:04
		oxalic	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 15:50
-	4575	(polymerization and poly(meth)acrylate and extraction) and aqueous near	USPAT; US-PGPUB;	2002/12/03 15:59
0		acid	EPO; JPO;	
			DERWENT	
_	78	((polymerization and poly(meth)acrylate and extraction) and aqueous	USPAT;	2002/12/03 15:59
	, 6	near acid) and ((polymerization and poly(meth)acrylate and extraction)	US-PGPUB;	
		and metal near remov\$3)	EPO; JPO;	
		·	DERWENT	
-	3585	(polymerization and poly(meth)acrylate and extraction) and photoresist	USPAT;	2002/12/03 16:09
			US-PGPUB;	
			EPO; JPO;	
	136	((, 1, , , , , , , , , , , , , , , , , ,	DERWENT USPAT;	2002/12/03 16:19
-	136	((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid	US-PGPUB;	2002/12/03 10.19
		and aqueous near acid	EPO; JPO;	
			DERWENT	
	1		1	

	,		HCDAT.	2002/12/02 14:21
*	496582	poly(meth)acrylate with reduc\$4 near metal near content	USPAT; US-PGPUB;	2002/12/03 16:21
			EPO; JPO;	
			DERWENT	2002/12/02 16 22
-	496590	poly(meth)acrylate with reduc\$4 with metal with content	USPAT;	2002/12/03 16:22
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 16:22
-	1844	(poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3	USPAT;	2002/12/03 16:23
_	1	with aqueous with acid	US-PGPUB;	
			EPO; JPO; DERWENT	
		((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3	USPAT;	2002/12/03 16:24
-	0	with aqueous with acid) and photoresist and solevnt near extraction	US-PGPUB;	2002/12/03 10.21
		with aqueous with acidy and photoresist and solevin near extraction	EPO; JPO;	
			DERWENT	
_	0	((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3	USPAT;	2002/12/03 16:24
_		with aqueous with acid) and photoresist and solvent near extraction	US-PGPUB;	
		, , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT	
_	50	((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3	USPAT;	2002/12/03 16:29
		with aqueous with acid) and photoresist	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/02 17 20
-	18	((poly(meth)acrylate same photoresist same purif\$8) same metal same	USPAT;	2002/12/03 16:38
		content) and washing near3 acid	US-PGPUB;	
			EPO; JPO;	
		1 (0 1) (1)	DERWENT	2002/12/03 16:40
-	814287	process same reduc\$3 metal same poly(meth)acrylate	USPAT; US-PGPUB;	2002/12/03 10.40
			EPO; JPO;	
			DERWENT	
	870738	method same reduc\$3 metal same poly(meth)acrylate	USPAT;	2002/12/03 17:02
-	8/0/38	method same reducts metal same poly(meth)acrylate	US-PGPUB;	2002/12/05 11/02
			EPO; JPO;	
			DERWENT	
_	792291	process same reduc\$3 metal same content same poly(meth)acrylate	USPAT;	2002/12/03 16:57
	.,,		US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	32	(process same reduc\$3 metal same content same poly(meth)acrylate) and	USPAT;	2002/12/03 16:42
		wash near aqueous near acid	US-PGPUB;	
*			EPO; JPO;	0
		1 62 (1 1 1 (1) - 1 1 - 1	DERWENT	2002/12/03 16:57
-	797019	process same reduc\$3 metal same content and poly(meth)acrylate	USPAT; US-PGPUB;	2002/12/03 10.37
			EPO; JPO;	
			DERWENT	
	660739	process same reduc\$3 metal same content	USPAT;	2002/12/03 16:59
	000739	process sume reduces mean sume content	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	2	contact\$3 near solvent near aqueous near acid	USPAT;	2002/12/03 16:59
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	0000/10/00 17 01
-	3600	(process same reduc\$3 metal same content) and polymethacrylate	USPAT;	2002/12/03 17:01
			US-PGPUB;	
			EPO; JPO;	
		1.00.1.1.1.1.1.1.1.1.1.1.1.1.1.1.1.1.1.	DERWENT	2002/12/03 17:00
-	0	((process same reduc\$3 metal same content) and polymethacrylate) and	USPAT; US-PGPUB;	2002/12/03 17:00
		(extract\$4 near solvent near aqueous near acid)	EPO; JPO;	
			DERWENT	
			DUK WENT	J

	15	extract\$4 near solvent near aqueous near acid	USPAT; US-PGPUB;	2002/12/03 17:00
			EPO; JPO;	
			DERWENT	
_	166	((process same reduc\$3 metal same content) and polymethacrylate) and	USPAT;	2002/12/03 17:01
	100	photoresist	US-PGPUB;	
		photoresist	EPO; JPO;	
			DERWENT	
	2500	(2002/12/03 17:02
-	2590	(method same reduc\$3 metal same poly(meth)acrylate) and ((process	USPAT;	2002/12/03 17:02
		same reduc\$3 metal same content) and polymethacrylate)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	138	((method same reduc\$3 metal same poly(meth)acrylate) and ((process	USPAT;	2002/12/03 17:05
		same reduc\$3 metal same content) and polymethacrylate)) and photoresist	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1	polyacrylate with reduced with metal with content	USPAT;	2002/12/03 17:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	496728	poly(meth)acrylate with reduced with metal with content	USPAT;	2002/12/03 17:06
-	470728	poly(metr)acrylate with reduced with metal with content	US-PGPUB;	2002/12/03 17.00
			EPO; JPO;	
	31			
			DERWENT	2002/12/02 17 06
-	0	polymethacrylate with reduced with metal with content	USPAT;	2002/12/03 17:06
	1		US-PGPUB;	
			ÉPO; JPO;	
			DERWENT	
-	5	acrylate with reduced with metal with content	USPAT;	2002/12/03 17:08
	3		US-PGPUB;	
			EPO; JPO;	
}			DERWENT	
-	225	polymer with reduc\$3 with metal with content	USPAT;	2002/12/03 17:09
			US-PGPUB;	
4.		·	EPO; JPO;	
			DERWENT	
_	142	polymer with reduced with metal with content	USPAT;	2002/12/03 17:10
-	142	polymer with reduced with metal with content	US-PGPUB;	2002/12/03 17:10
			EPO; JPO;	
	2011006	m2 : 4.1 1.4	DERWENT	2002/12/03 17:28
-	3011096	remov\$3 metal near polyacrylate	USPAT;	2002/12/03 17:28
		•	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	removal near metal near polyacrylate	USPAT;	2002/12/03 17:12
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	35	metal near ions near removal and polyacrylate	USPAT;	2002/12/03 17:13
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	691	(remov\$3 metal near polyacrylate) and solvent near aqueous near acid	USPAT;	2002/12/03 17:25
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	229	((remov\$3 metal near polyacrylate) and solvent near aqueous near acid)	USPAT;	2002/12/03 17:25
-	229	and extraction	US-PGPUB;	2002112103 17.23
		and extraction		
1			EPO; JPO; DERWENT	
i			LIHW WHEN I	I .
	****	(1	2002/12/02 17 22
_	68007	(remov\$3 metal near polyacrylate) and ion near exchange	USPAT;	2002/12/03 17:29
-	68007	(remov\$3 metal near polyacrylate) and ion near exchange	USPAT; US-PGPUB;	2002/12/03 17:29
-	68007	(remov\$3 metal near polyacrylate) and ion near exchange	USPAT;	2002/12/03 17:29

	2	("5466745").PN.	USPAT; US-PGPUB;	2002/12/03 17:44
				,
			EPO; JPO;	
			DERWENT	2002/12/02 17:27
-	1	("60005045").PN.	USPAT;	2002/12/03 17:37
			US-PGPUB;	
	1		EPO; JPO;	
			DERWENT	2002/12/02 17:27
-	2	("6005045").PN.	USPAT;	2002/12/03 17:37
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/03 17:42
-	2	("6046276").PN.	USPAT;	2002/12/03 17:42
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/12/03 17:43
-	2	("5916992").PN.	USPAT;	2002/12/03 17.43
			US-PGPUB;	
			EPO; JPO; DERWENT	
				2002/12/03 17:44
j -	2	(("5466745").PN.)	USPAT; US-PGPUB;	2002/12/03 17.44
			EPO; JPO;	
			DERWENT	
	_		USPAT;	2002/12/03 17:44
-	9	"5466745"	US-PGPUB;	2002/12/03 17.44
			EPO; JPO;	
			DERWENT	
]		USPAT;	2002/12/04 10:09
-	350	polymeriz\$5 same acrylate same aqueous same acid same solvent	US-PGPUB;	2002/12/04 10.07
			EPO; JPO;	
			DERWENT	
	_	the state of the s	USPAT;	2002/12/04 10:09
-	5	(polymeriz\$5 same acrylate same aqueous same acid same solvent) and	US-PGPUB;	2002/12/04 10:07
		photoresist	EPO; JPO;	
			DERWENT	
	2.	t ' 65	USPAT;	2002/12/04 10:14
-	31	polymeriz\$5 same acrylate same extract\$3 same aqueous same acid	US-PGPUB;	2002/12/01/10/1
			EPO; JPO;	
			DERWENT	
	1.0	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 10:15
-	18		US-PGPUB;	2002/12/01/100
		photoresist	EPO; JPO;	
			DERWENT	
	220	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	USPAT;	2002/12/04 10:17
_	220	polymenzas same acrytate same wasnes same aqueous same acra	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	19	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 10:17
-	17	photoresist	US-PGPUB;	
	1	photoconst	EPO; JPO;	
			DERWENT	
_	7	Synthesi\$4 same acrylate same wash\$3 same aqueous same acid	USPAT;	2002/12/04 10:19
] -	/		US-PGPUB;	
			EPO; JPO;	
			DERWENT	1
_	204	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	USPAT;	2002/12/04 12:24
	20.		US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	4	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 10:20
		metal near remov\$3	US-PGPUB;	
			EPO; JPO;	
			DERWENT	1

-	129596	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and maleic or fumaric or oxalic or malonic or adipic near acid	USPAT; US-PGPUB;	2002/12/04 12:26
		matere or lumaric or oxalic or matoric of adipte near acto	EPO; JPO;	
			DERWENT	
	115	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 12:49
-	115	(maleic or fumaric or oxalic or malonic or adipic near acid)	US-PGPUB;	2002/12/04 12.49
		(matere or rumane of oxane of matorite of adipte hear acid)	EPO; JPO;	
			DERWENT	
	7	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 12:51
-	/	oxalic near acid	US-PGPUB;	2002, 12, 01, 12.31
		Oxano near dela	EPO; JPO;	
			DERWENT	
1_	0	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and	USPAT;	2002/12/04 13:01
		aqueous near oxalic	US-PGPUB;	
			EPO; JPO;	
1			DERWENT	
1 -	19	"4089806"	USPAT;	2002/12/04 13:05
Î			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	9	"4122000"	USPAT;	2002/12/04 13:43
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	88	metal near remov\$3 near chelat\$3	USPAT;	2002/12/04 13:44
			US-PGPUB;	
			EPO; JPO;	
	_		DERWENT	2002/12/04 15 20
-	2	(metal near remov\$3 near chelat\$3) and oxalic	USPAT;	2002/12/04 15:29
1			US-PGPUB;	
			EPO; JPO; DERWENT	
		(#5072(20H) DNI		2002/12/04 15:33
-	2	("5073622").PN.	USPAT; US-PGPUB;	2002/12/04 15.55
			EPO; JPO;	
			DERWENT	
	0	a356523	USPAT;	2002/12/04 15:34
-	0	4330323	US-PGPUB;	2002, 12, 00
			EPO; JPO;	
			DERWENT	
	0	a356523	JPO;	2002/12/04 15:34
1			DERWENT	
_	0	a0356523	JPO;	2002/12/04 15:34
			DERWENT	
-	13	"0356523"	JPO;	2002/12/04 15:37
			DERWENT	
-	2	"03056523"	JPO;	2002/12/04 15:50
			DERWENT	•
	2	("4522928").PN.	USPAT;	2002/12/04 15:50
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	